

REMARKS/ARGUMENTS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1-8 are presently active; Claims 1 and 5 have been amended by the present amendment.

In the outstanding Office Action, the specification was objected due to informalities. Claims 1-4 were rejected under 35 U.S.C. § 102(b) as being anticipated by Hattori et al. (U.S. Pat. No. 4,996,458). Claims 5-8 were rejected to under 35 U.S.C. § 103(a) as being unpatentable over Hattori et al.

Regarding the objection to the specification, the specification has been amended as suggested in the outstanding Office Action. Thus, it is respectfully submitted that the objection to the specification has been overcome.

Regarding the rejection to the Claim 1-8, Applicants respectfully traverse the outstanding grounds for rejection, because in Applicants' view, the independent claims 1 and 5 patentably distinguish over the applied prior arts. In light of the outstanding grounds for rejection, to expedite issuance of a patent from the present application, Claim 1 and 5 have been amended. No new matter has been added.

Firstly, Claim 1 and 5 recite the auxiliary mask fixed to a region containing the minor axis of the effective portion of the main mask. The auxiliary has a width in the direction of the major axis smaller than a length of the effective portion of the main mask in the direction of the major axis. Instead, Hattori et al. discloses that, as clearly shown in, for example, FIG. 11(b), the main mask (sheet 21) and the auxiliary mask (sheet 22) of shadow mask 7 are formed in the same size and the auxiliary mask (sheet 22) is fixed to the entire surface of the main mask (sheet 21). Thus, Hattori et al. does not disclose the auxiliary mask having a width in the

direction of the major axis smaller than a length of the effective portion of the main mask in the direction of the major axis.

Second, Claims 1 and 5 recite the smaller and larger holes of each electron beam passage aperture of the auxiliary mask individually having central axes extending coaxially with each other and substantially at right angles to the surface of the auxiliary mask in the direction of the major axis. Instead, Hattori et al. discloses aperture (13) of auxiliary mask (22), the central axes of small and large holes of which extend not coaxially with but eccentrically from each other as clearly shown in FIG. 4 and described at column 13, lines 20-43. In FIG. 4 of Hattori et al., Ow1, Ow2, Ow3, and Ow4 are 150 μm , 120 μm , 250 μm , and 170 μm , respectively (see column 13, lines 34-36). Therefore, the central axis of the small hole is 15 μm to the right of the axis Q, while the central axis of the large hole is 40 μm to the right of the axis Q. Therefore, in Hattori et al., the central axes of the small and large holes of aperture (13) of auxiliary mask (22) extend not coaxially with each other. Thus, Hattori et al. does not disclose the smaller and larger holes of each electron beam passage aperture of the auxiliary mask individually having central axes extending coaxially with each other and substantially at right angles to the surface of the auxiliary mask in the direction of the major axis. In view of this deficiency, it is respectfully submitted that Claims 1 and 5 patentably distinguish over Hattori et al.

The remaining pending Claims 2-4 dependent from Claim 1 and Claims 6-8 dependent from Claim 5 are there believed to be allowable.

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Consequently, in view of the present amendment and in light of the above discussions, the outstanding grounds for rejection are believed to have been overcome. The application as amended herewith is believed to be in condition for formal allowance. An early and favorable action to that effect is respectfully requested.

Respectfully submitted,

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